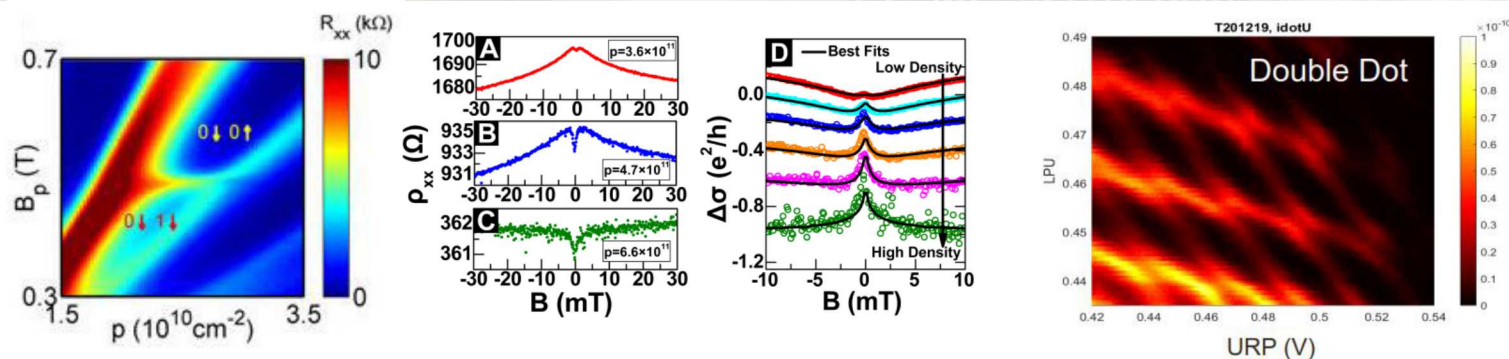




Holes in Germanium Quantum Wells and Their Potential Applications in Quantum Computing



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Acknowledgements

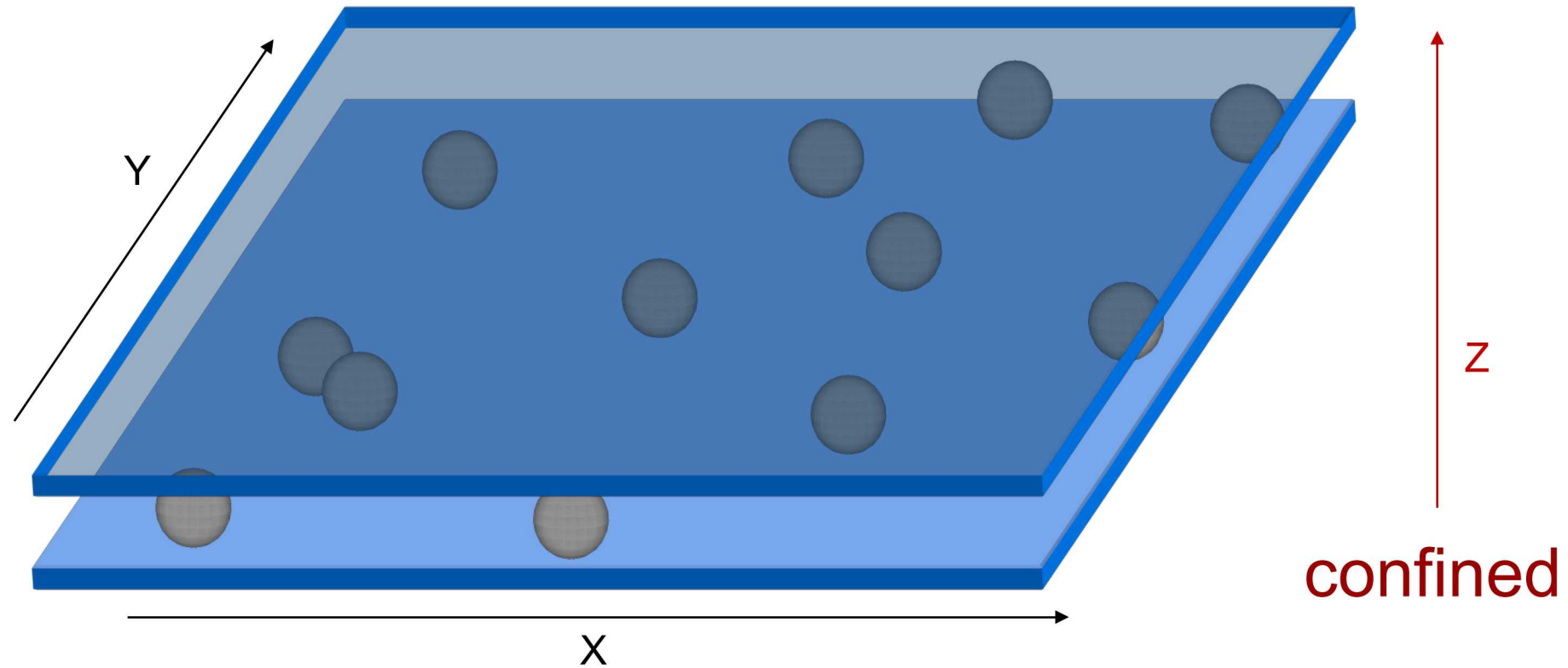
- Sandia National Laboratories: M. P. Lilly, D. Laroche, L. A. Tracy, C. T. Harris, N. T. Jacobson, J. Moussa, A. D. Baczewski, D. R. Luhman, W. Hardy, and L. N. Maurer.
- National Taiwan University: C. W. Liu, J.-Y. Li, C.-H. Lee, S.-H. Huang, Y. Chuang, Y.-H. Su, C.-T. Chou
- NHMFL

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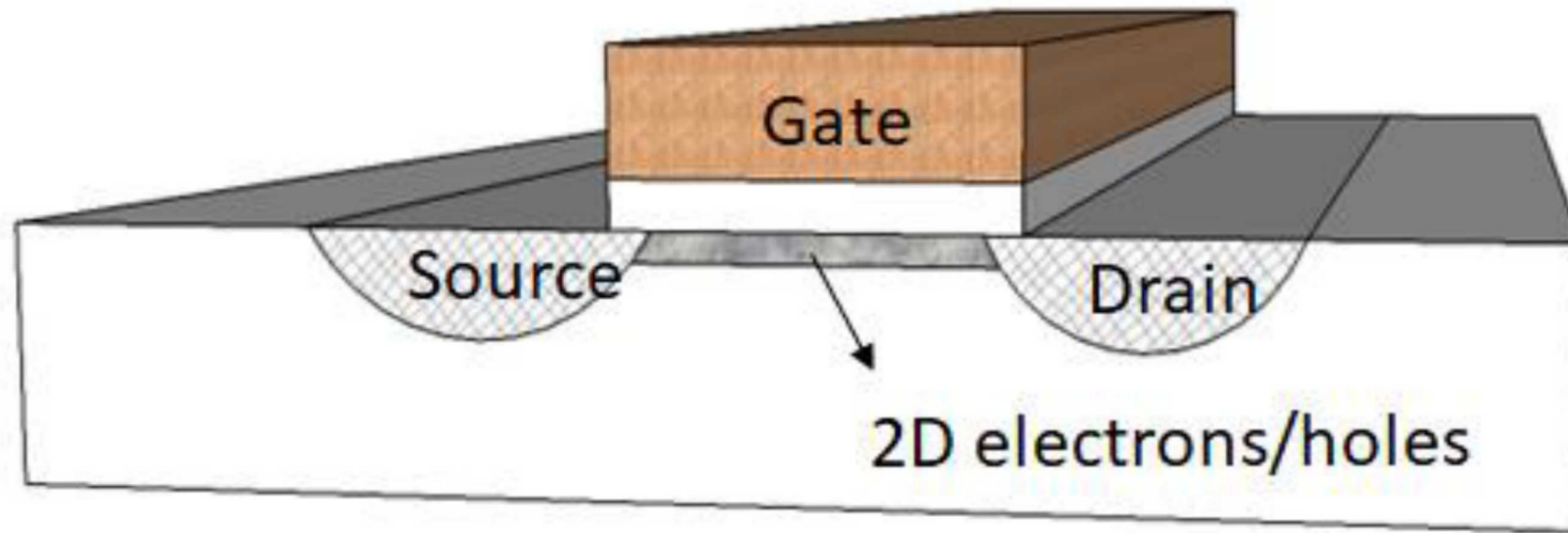
Outline

- Ge/SiGe heterostructures
- Device operation
- Properties of 2D holes in Ge/SiGe
- Quantum Hall ferromagnetic transition
- Spin qubits in Ge/SiGe
- Summary

2D electrons/holes

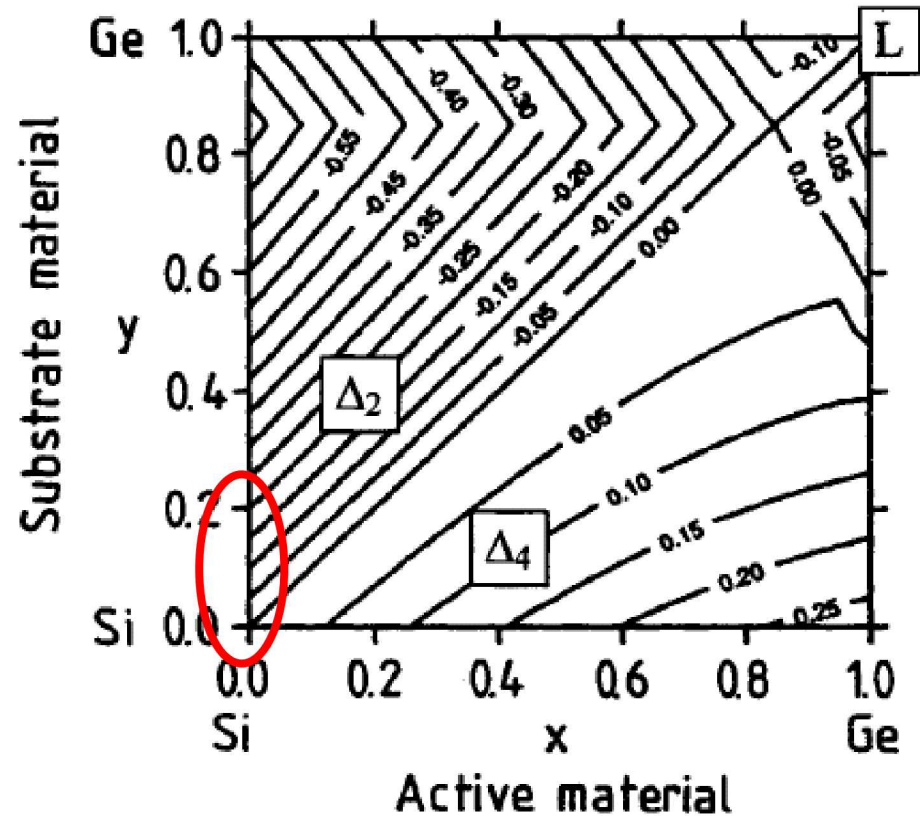


Si MOSFET



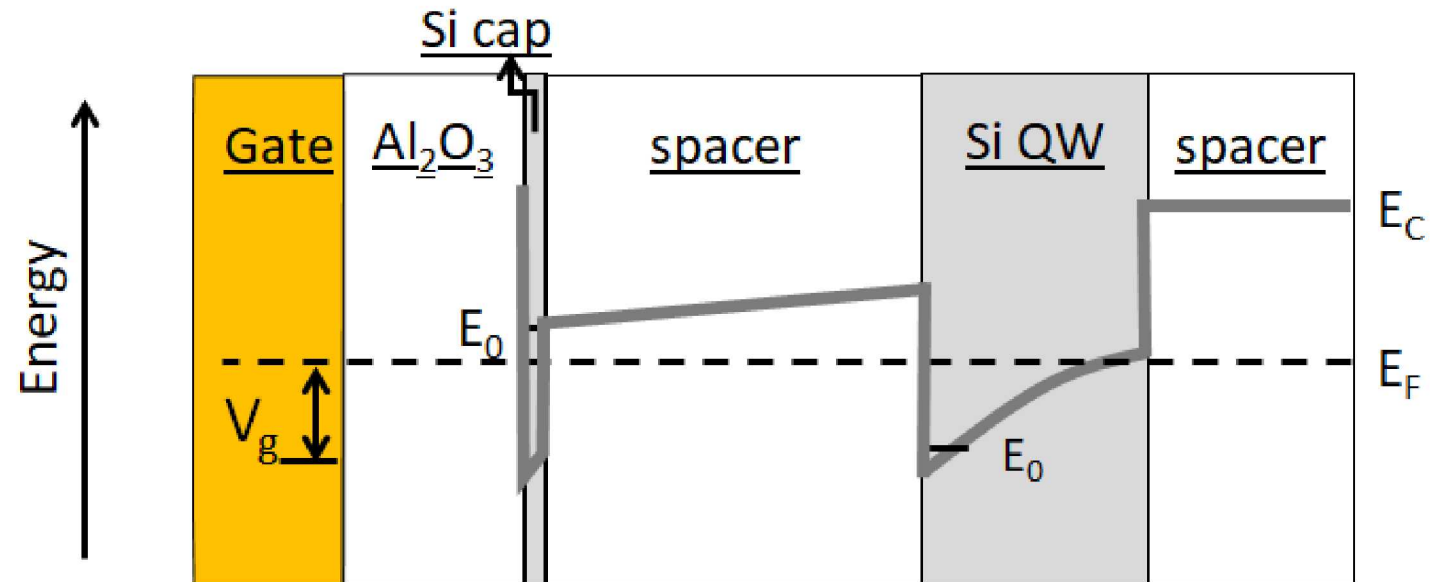
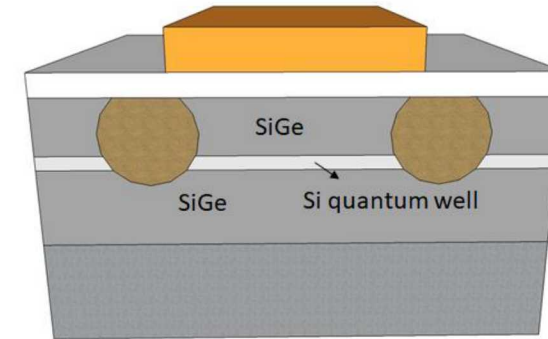
Band alignment of Si/SiGe heterostructures

Conduction band (a)

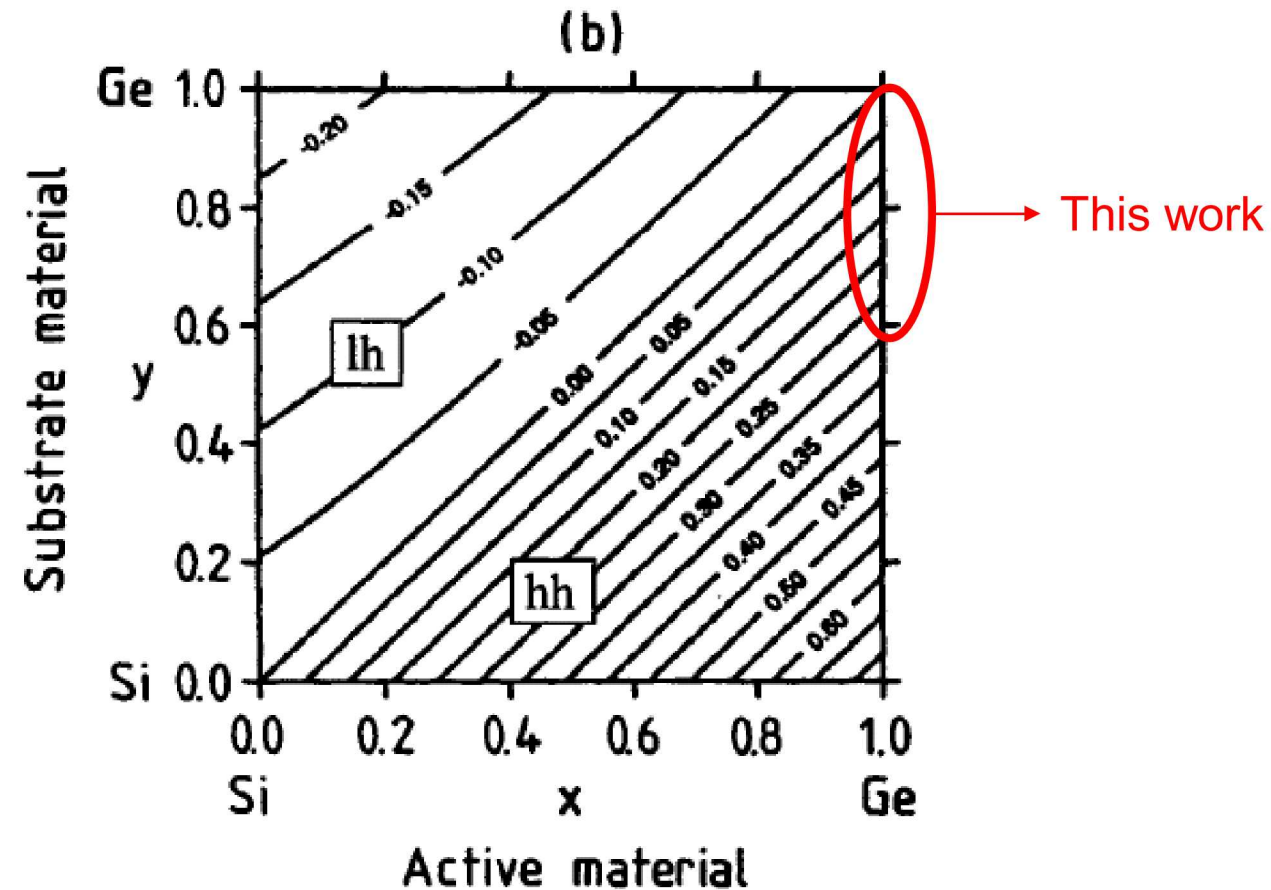


2D electrons in Si quantum wells

Undoped Si/SiGe HFET

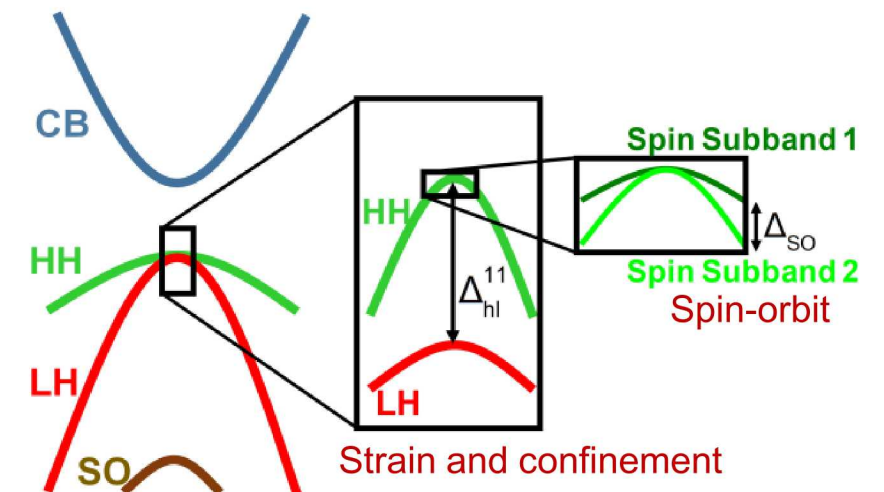
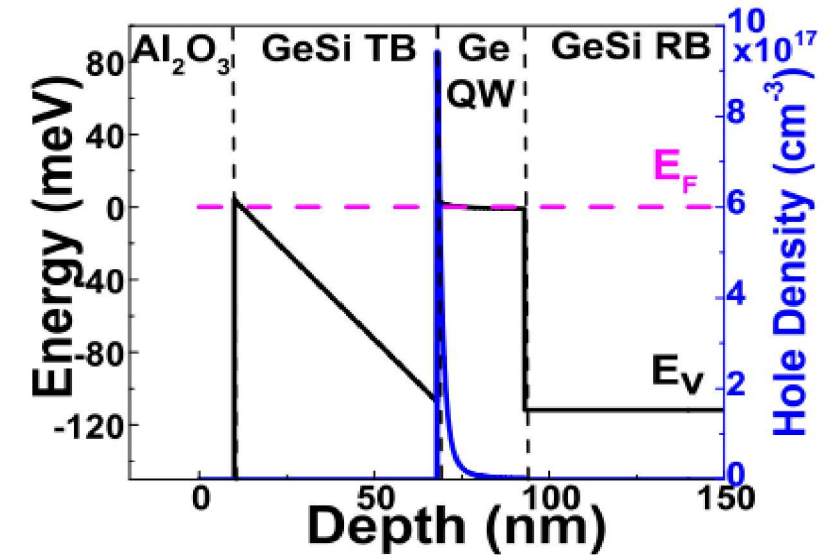
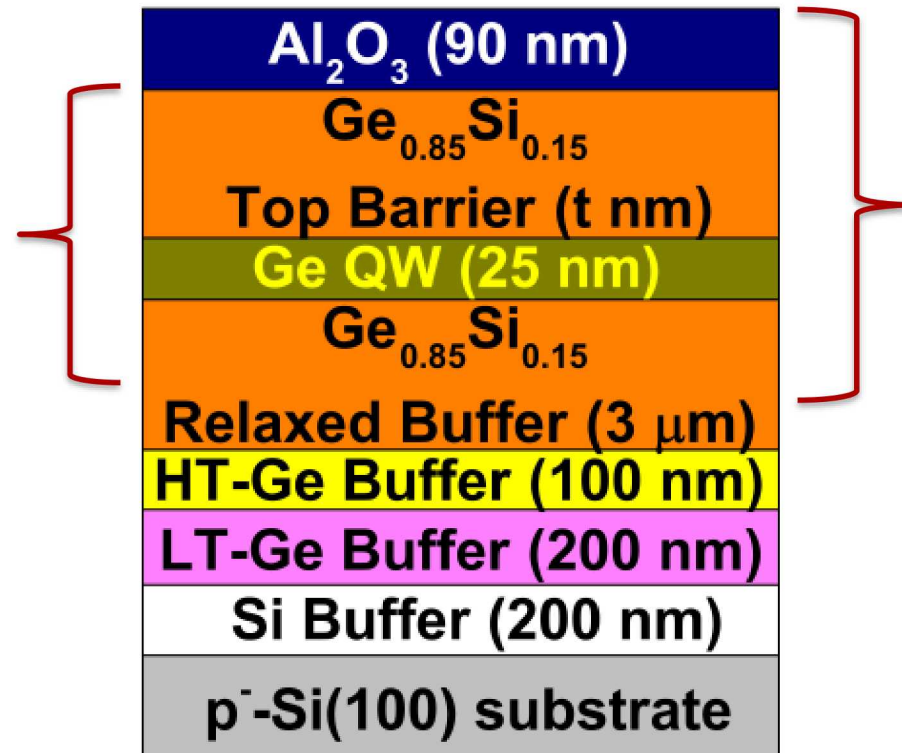
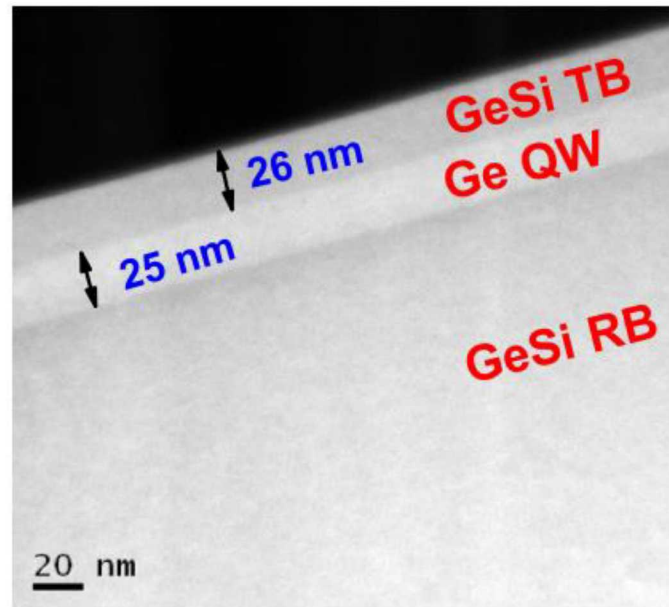


Band alignment of Ge/SiGe heterostructures



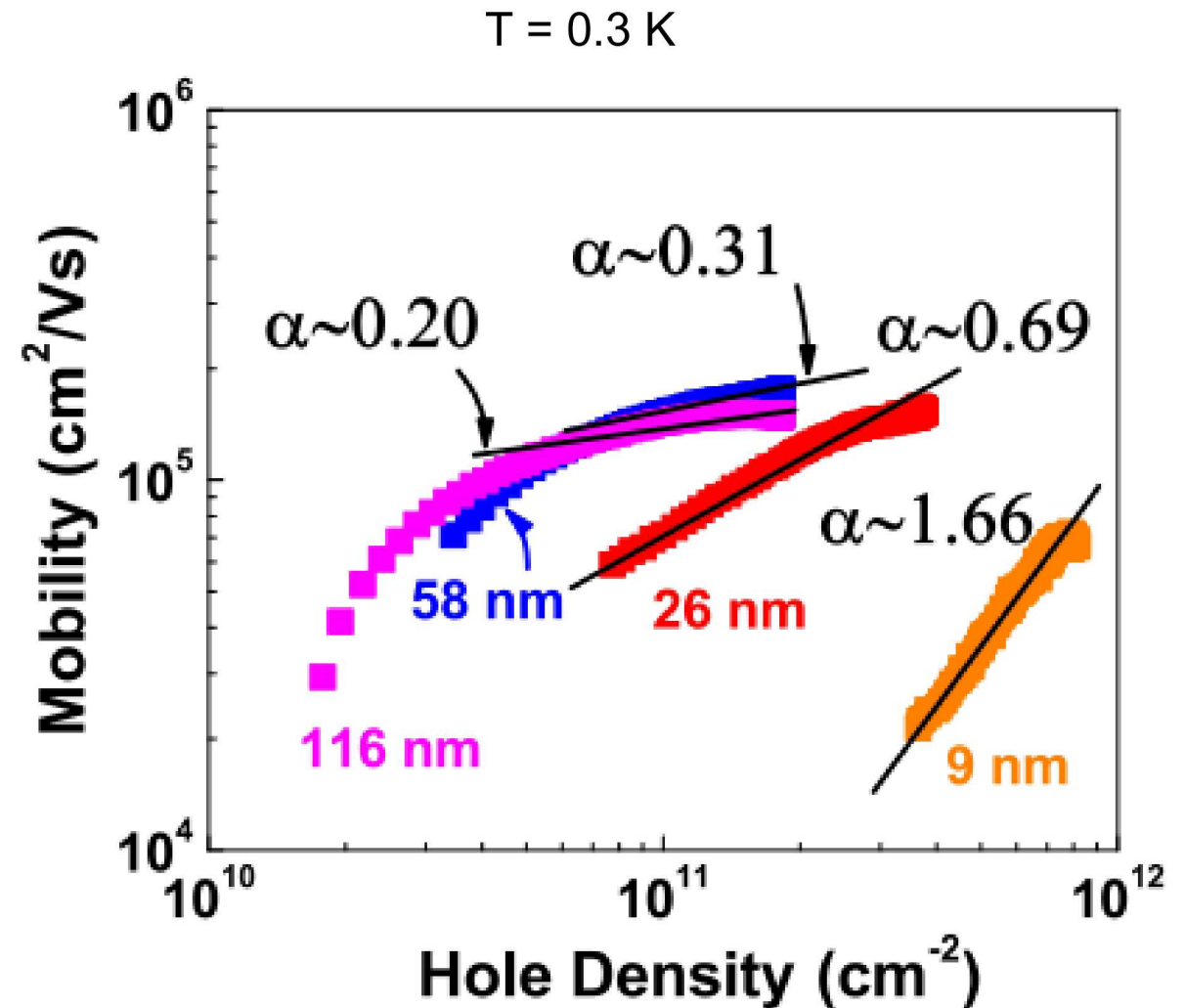
Valance band
2D holes in Ge quantum wells

Undoped Ge/SiGe heterostructure field-effect transistors



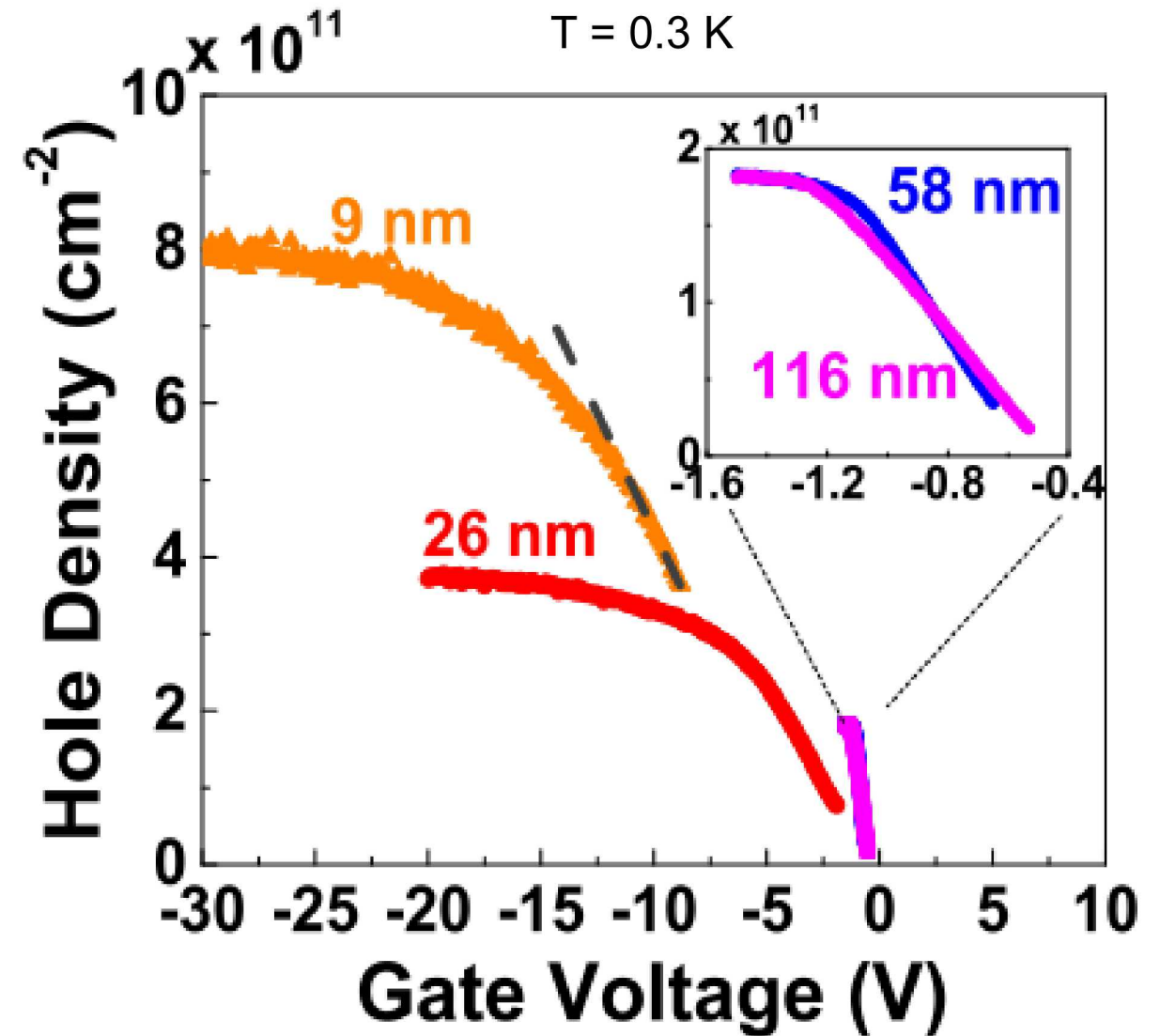
Device operation – mobility

- Mobility on the order of $2 \times 10^5 \text{ cm}^2/\text{Vs}$ achievable
- Mobility increases with density
=> screening
- Shallower channels have lower mobilities
=> oxide/GeSi interface is disordered

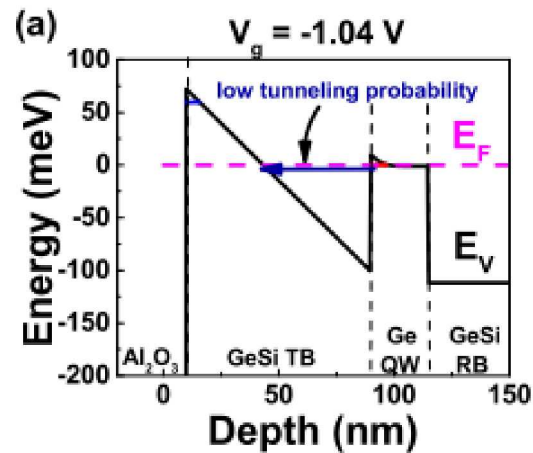


Device operation – 2D hole density

- The 2D hole density saturates.
- Shallow channels
 - High saturation densities, depth dependent.
 - Small slopes (capacitances)
- Deep channels
 - Low saturation densities, depth independent.
 - Large slopes (capacitances)



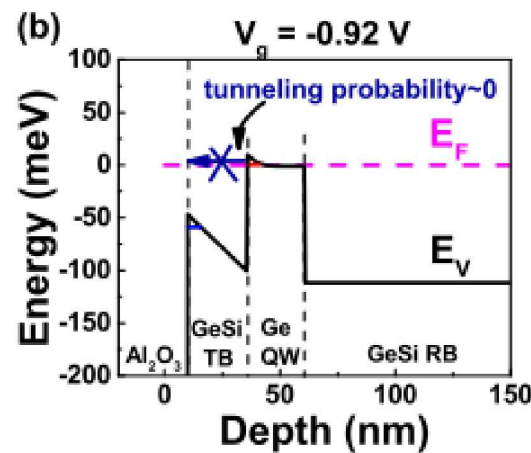
Device operation – 2D hole density



Deep channels

The tunnel rate is **limited by triangular barrier** (set by Si%) and is **depth independent**.

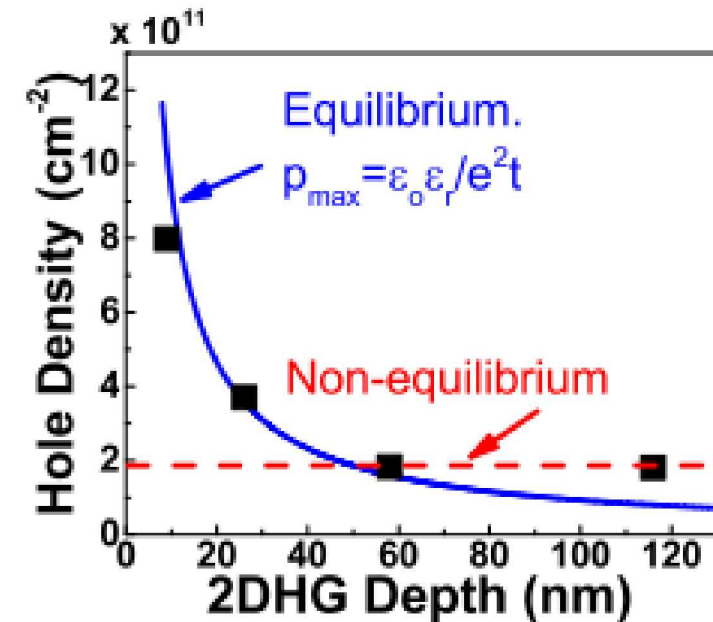
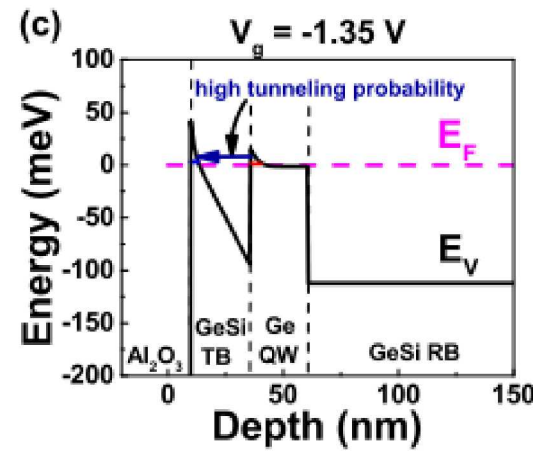
The **tunnel rate can be so low** that the density only slowly decreases and **never reaches equilibrium** at low temperatures!



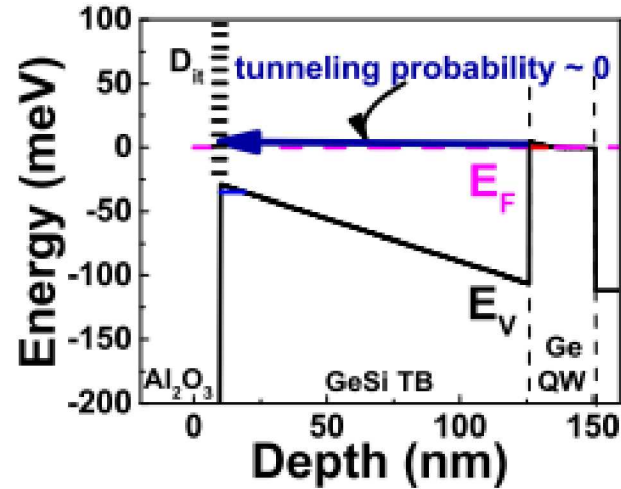
Shallow channels

The **tunneling rate is high** (compared to experiment time scales).

The density probed by the Hall effect approaches the **equilibrium** case.



Device operation – 2D hole density

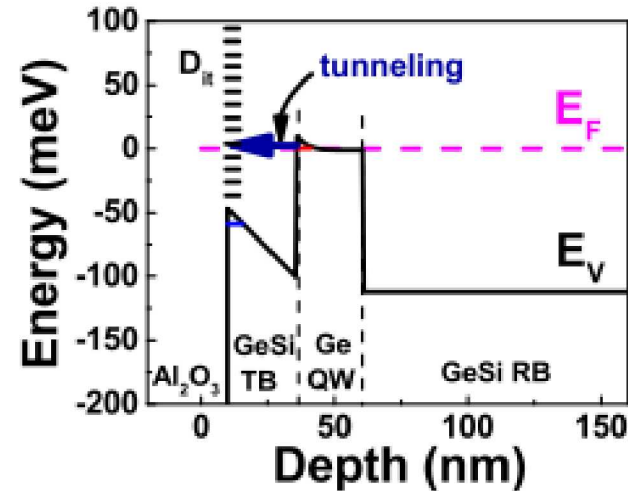


Deep channels

The tunnel rate is **low**.

The traps at the oxide/GeSi interface **do not (need to) get filled**.

$$C_{\text{eff}} \sim C_{\text{geometric}}$$

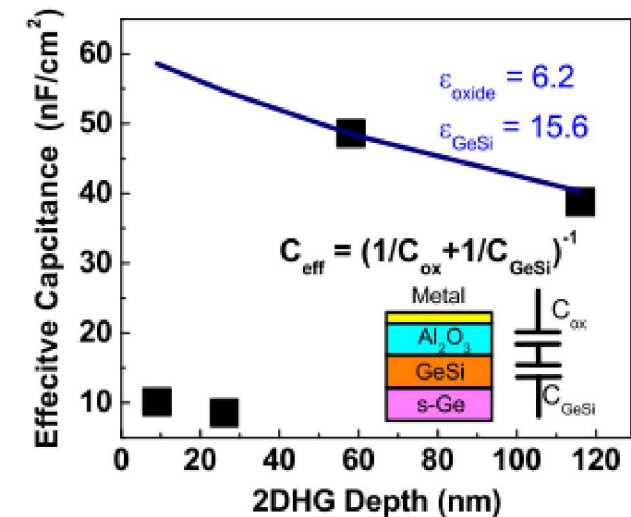
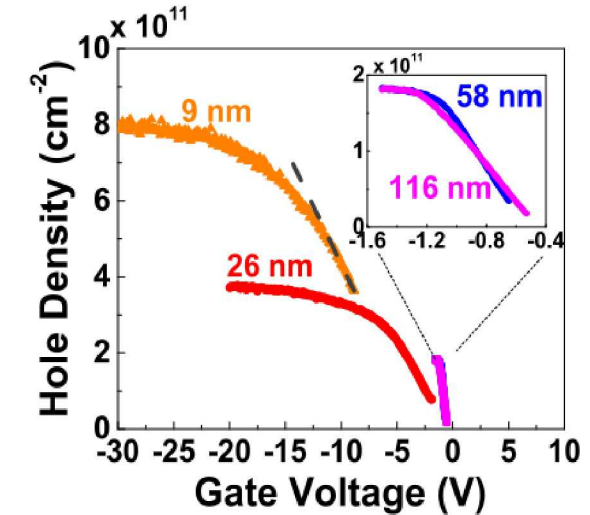


Shallow channels

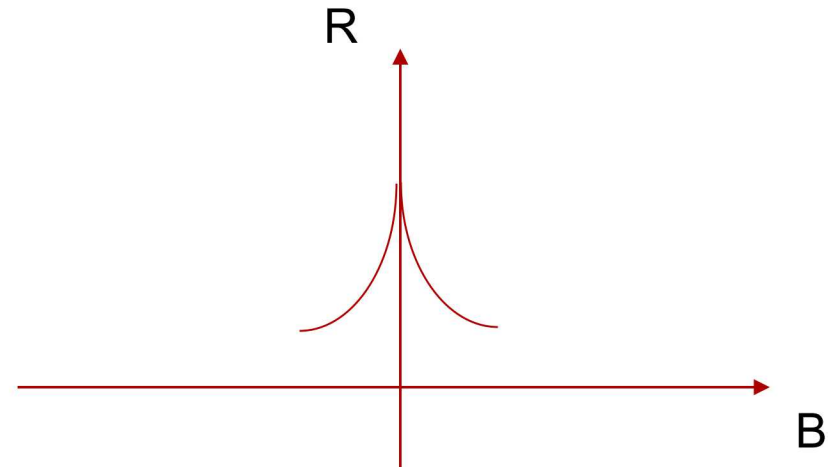
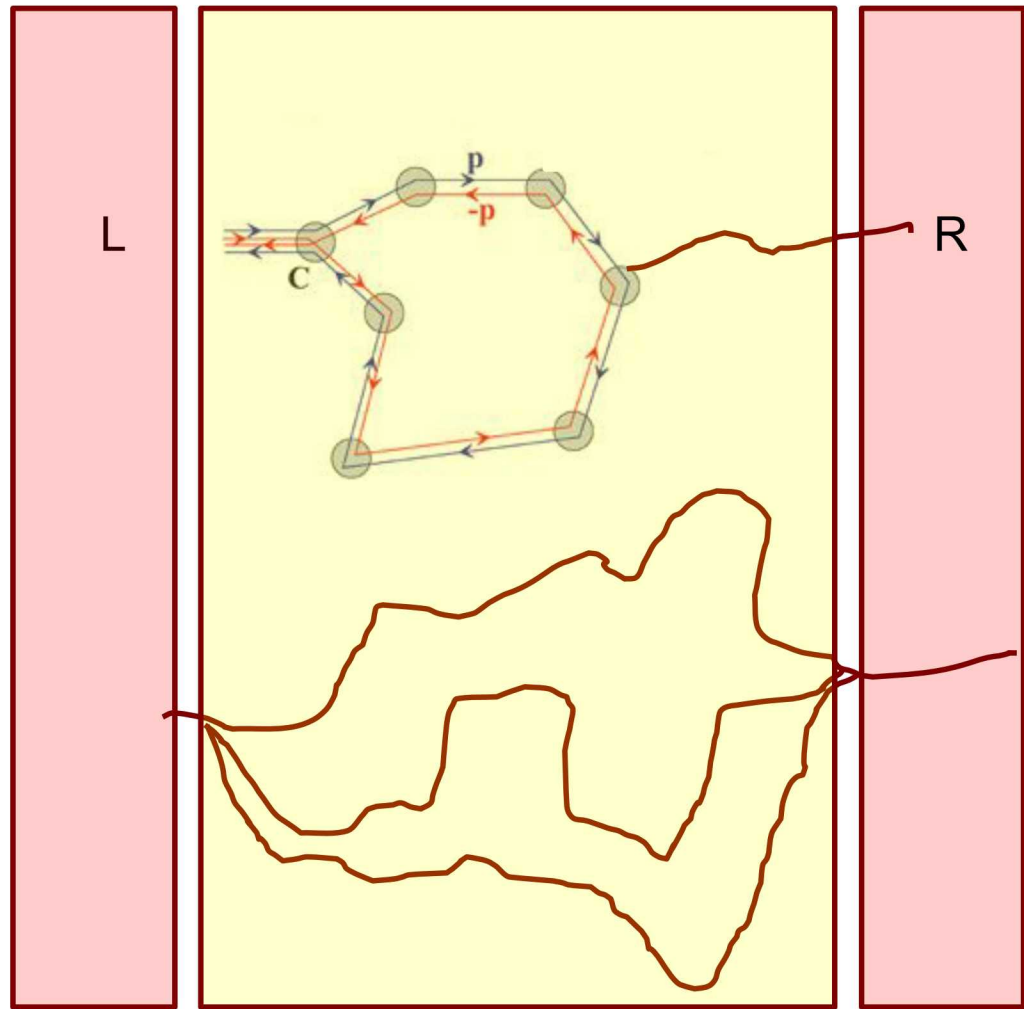
The tunnel rate is **high**.

The traps at the oxide/GeSi interface **need to be filled** before the Fermi level can move.

$$C_{\text{eff}} \ll C_{\text{geometric}}$$

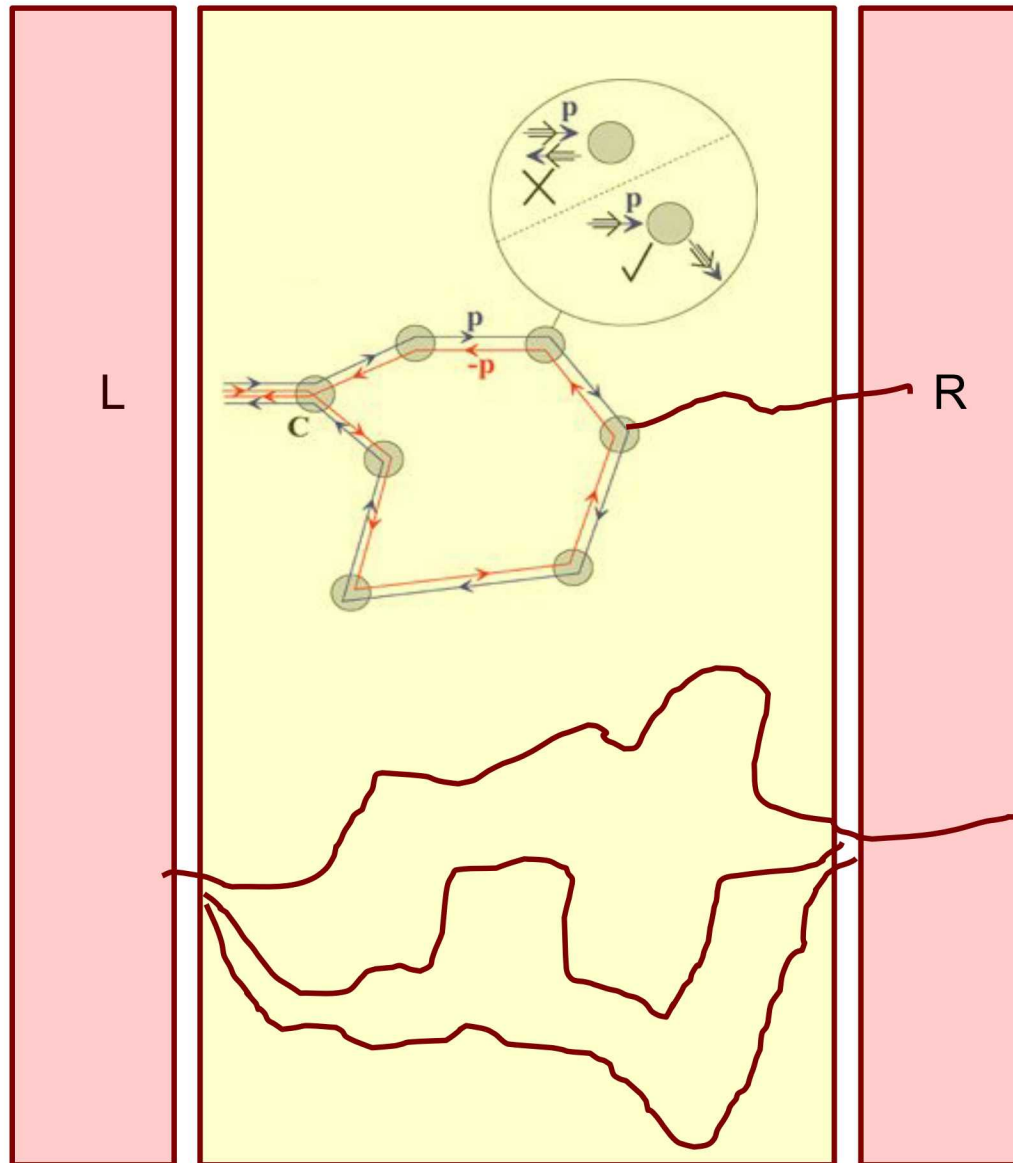


Weak localization (no spin-orbit coupling)

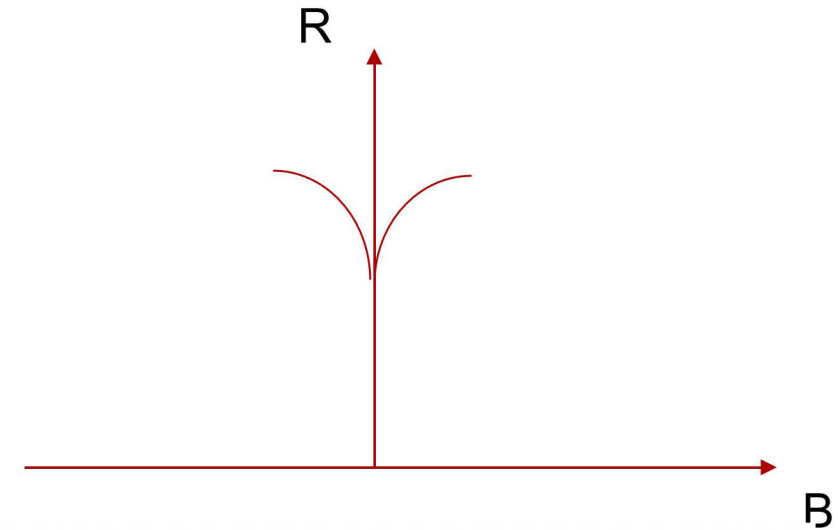


Adapted from McCann Physics 2, 98

Weak anti-localization (spin-orbit coupling)



Spin and momentum are locked together.
Back scattering is suppressed.



$$\Delta\sigma(B) - \Delta\sigma(0) = \frac{e^2}{2\pi^2\hbar} \left\{ \psi\left(\frac{1}{2} + \frac{H_\varphi}{B} + \frac{H_{SO}}{B}\right) + \frac{1}{2} \psi\left(\frac{1}{2} + \frac{H_\varphi}{B} + \frac{2H_{SO}}{B}\right) - \frac{1}{2} \psi\left(\frac{1}{2} + \frac{H_\varphi}{B}\right) - \ln \frac{H_\varphi + H_{SO}}{B} - \frac{1}{2} \ln \frac{H_\varphi + 2H_{SO}}{B} + \frac{1}{2} \ln \frac{H_\varphi}{B} \right\}$$

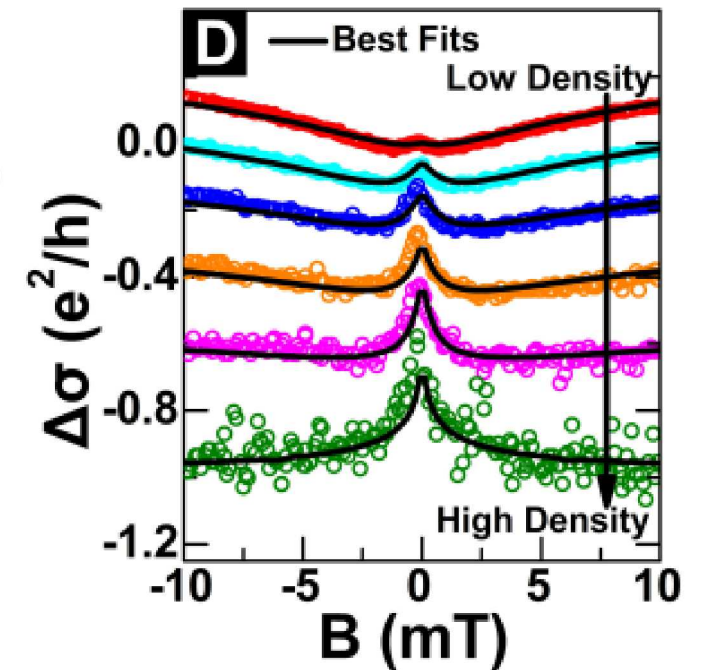
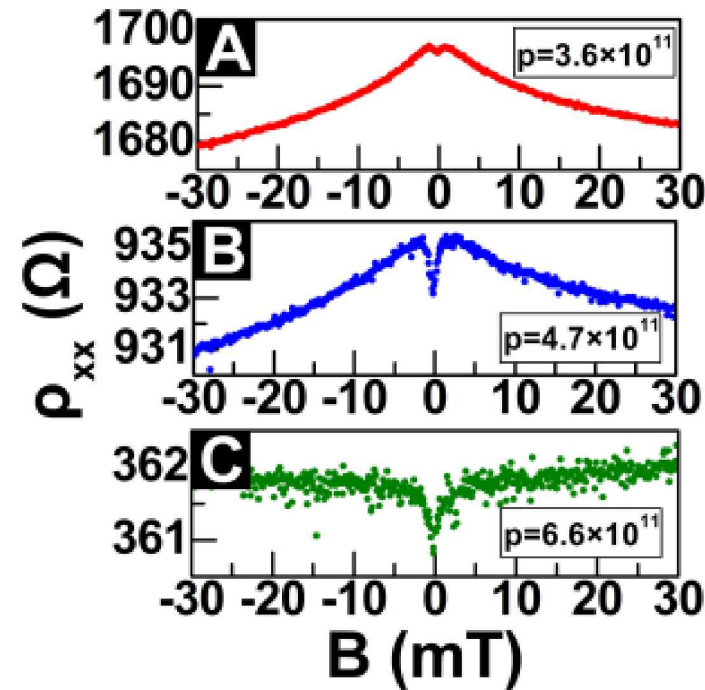
Hikami Prog. Theor. Phys. 63, 707

Adapted from McCann Physics 2, 98

Physical properties – spin-orbit coupling

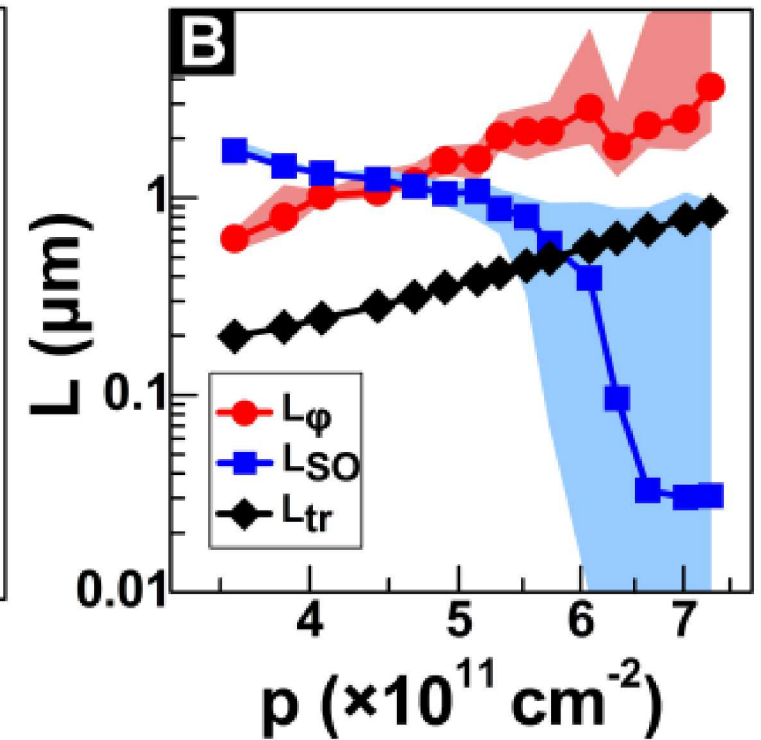
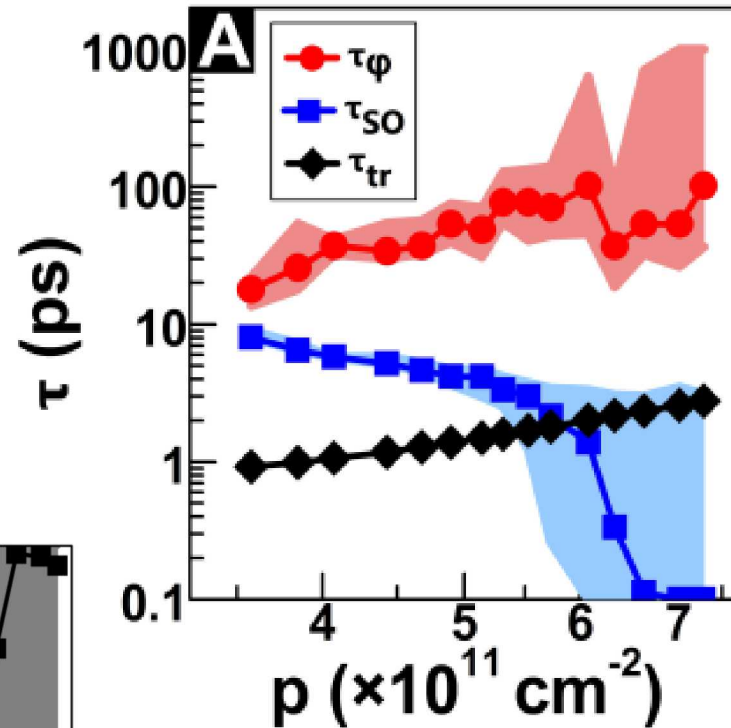
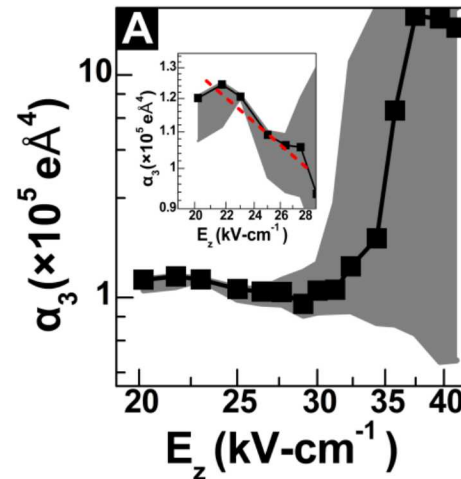
- Low densities
 - Weak localization only
- Intermediate densities
 - Weak anti-localization on top of weak localization only
- High densities
 - Weak anti-localization only

Cubic Rashba: $\sim(\sin 3\theta, -\cos 3\theta)$



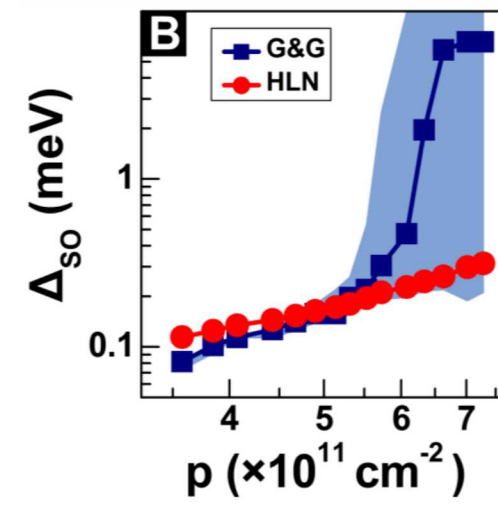
Physical properties – spin-orbit coupling

- Spin-orbit length decreases with density and can be as short as 0.1 μm ($<$ mean free path), while the phase coherence length can be a few microns long ($>$ mean free path)
- This means the hole spin can rotate at a high yet controlled rate, maintain its phase coherence, and suffer no scattering.



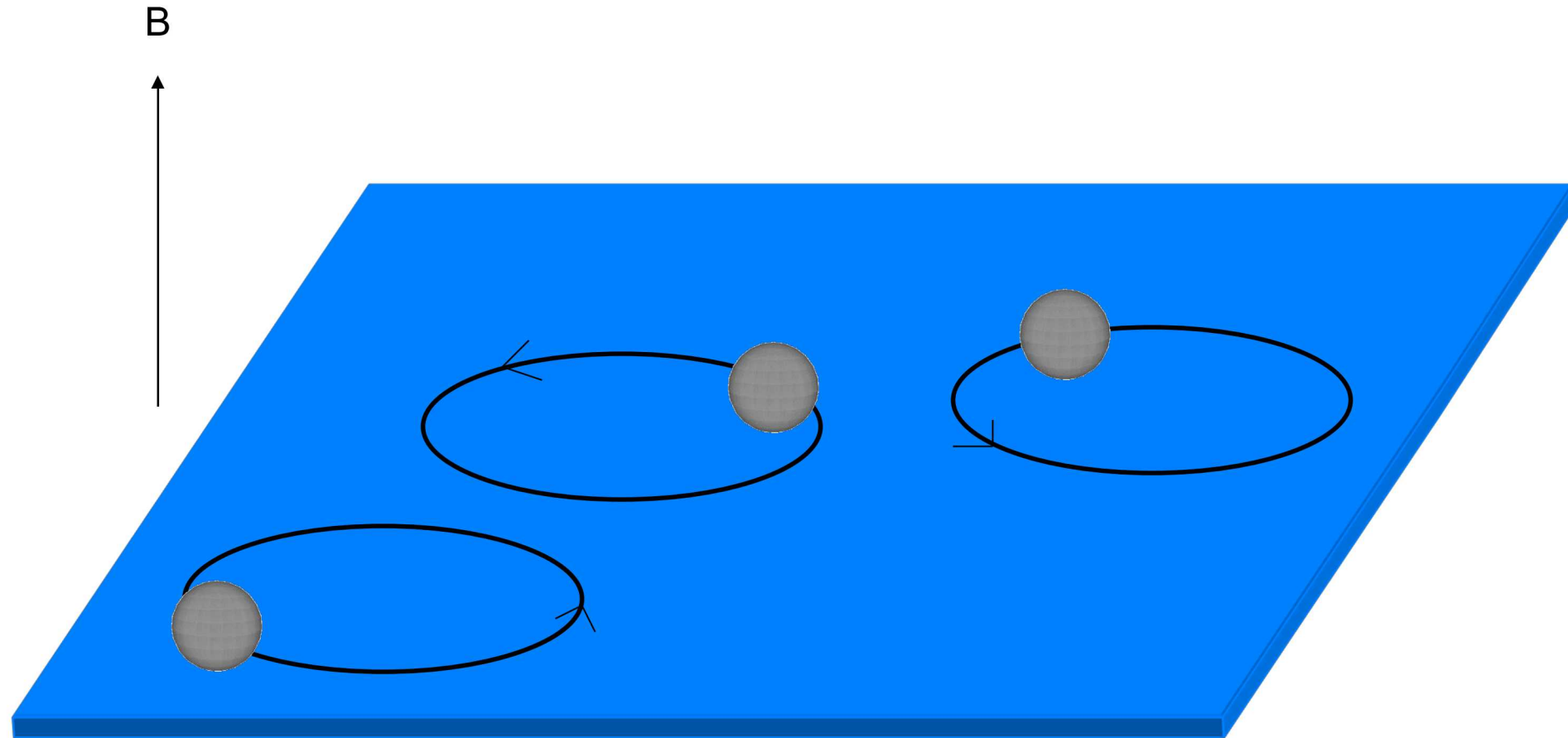
Physical properties – weak antilocalization beyond diffusive regime

- Conventional theories for weak (anti)localization are only valid in the diffusive regime at low magnetic fields.
- Our data lie outside this regime.
- Numerical methods and code for HPC available with paper.
-



Chou, Nanoscale 10, 20559 (2018)

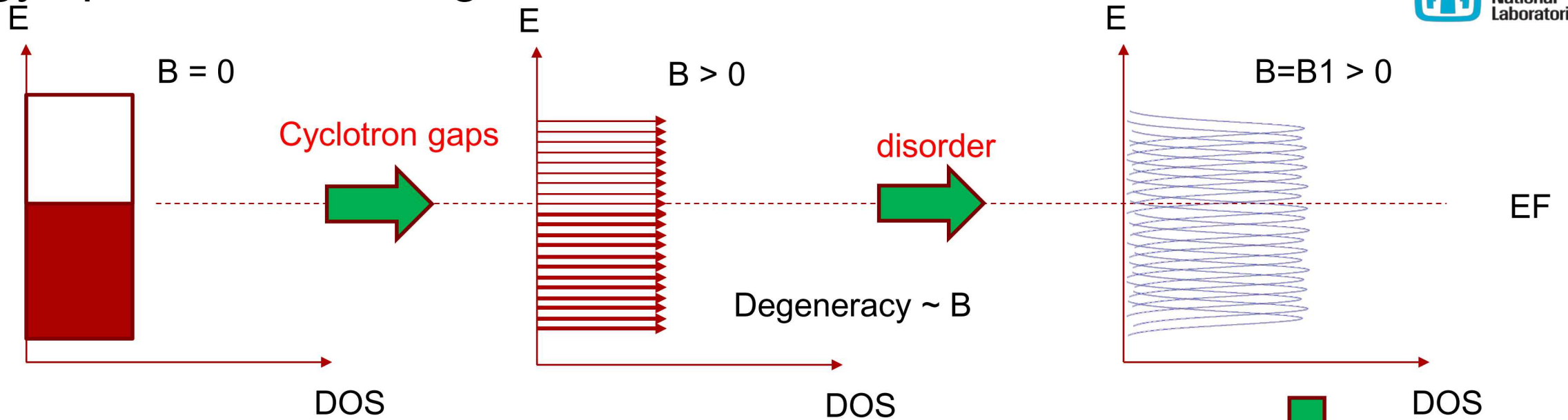
In a perpendicular magnetic field...



Cyclotron motion, $E_c = \hbar e B_{\text{perp}} / m^*$

Spin splitting, gap $E_z = g \mu B$

Energy spectrum in a magnetic field



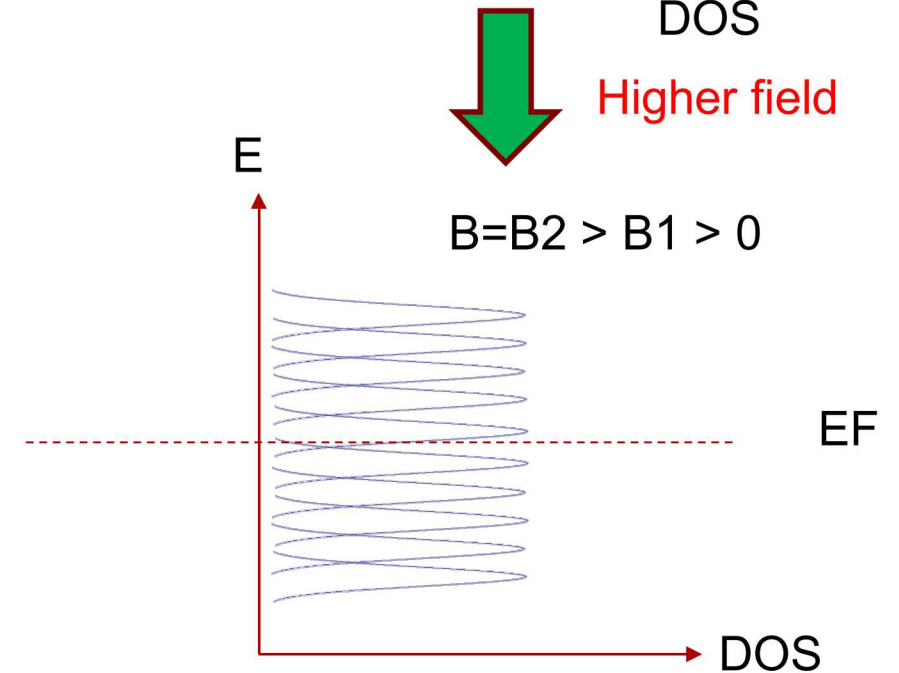
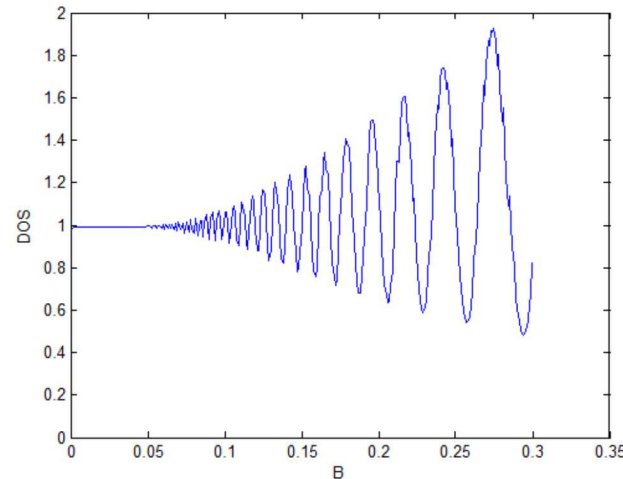
$$\frac{\Delta \rho}{\rho_0} \sim D(X) \frac{\Delta \text{DOS}}{\text{DOS}_0}$$

$$D(X) = X / \sinh X$$

$$X = 2\pi kT / \text{gap}$$

Temperature dependence
 $\Leftrightarrow$ gap

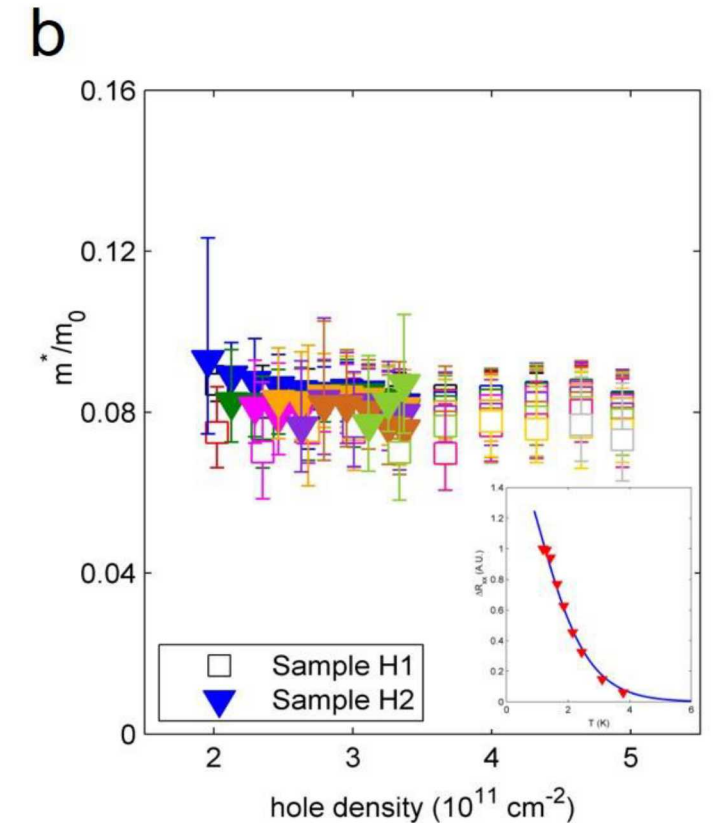
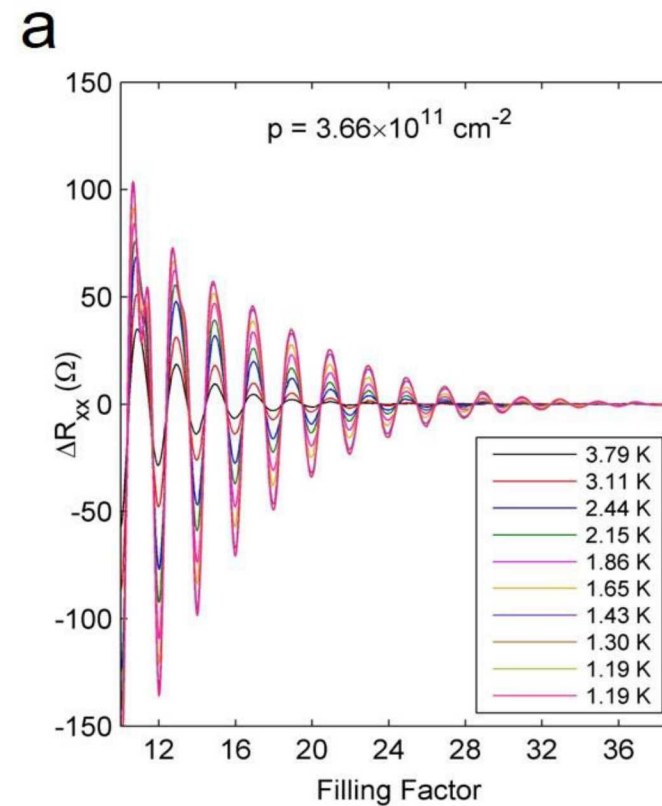
DOS at Fermi energy at a fixed density



Physical properties – effective mass

- $\sim 0.08 m_0$.
- $\sim$ density independent.
- This mass is small compared to the mass of electrons in Si (0.19), the mass of holes in GaAs (0.2-0.4), and is comparable to the mass of electrons in GaAs (0.07).
- Smaller mass
 => more extended wave functions
 => easier gate controls for nanostructures

 => larger orbital gaps
 => can use higher T cryostats



Physical properties – effective mass

Theory

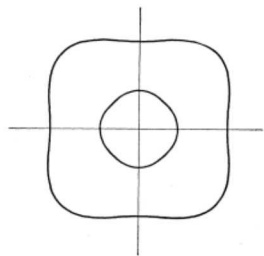
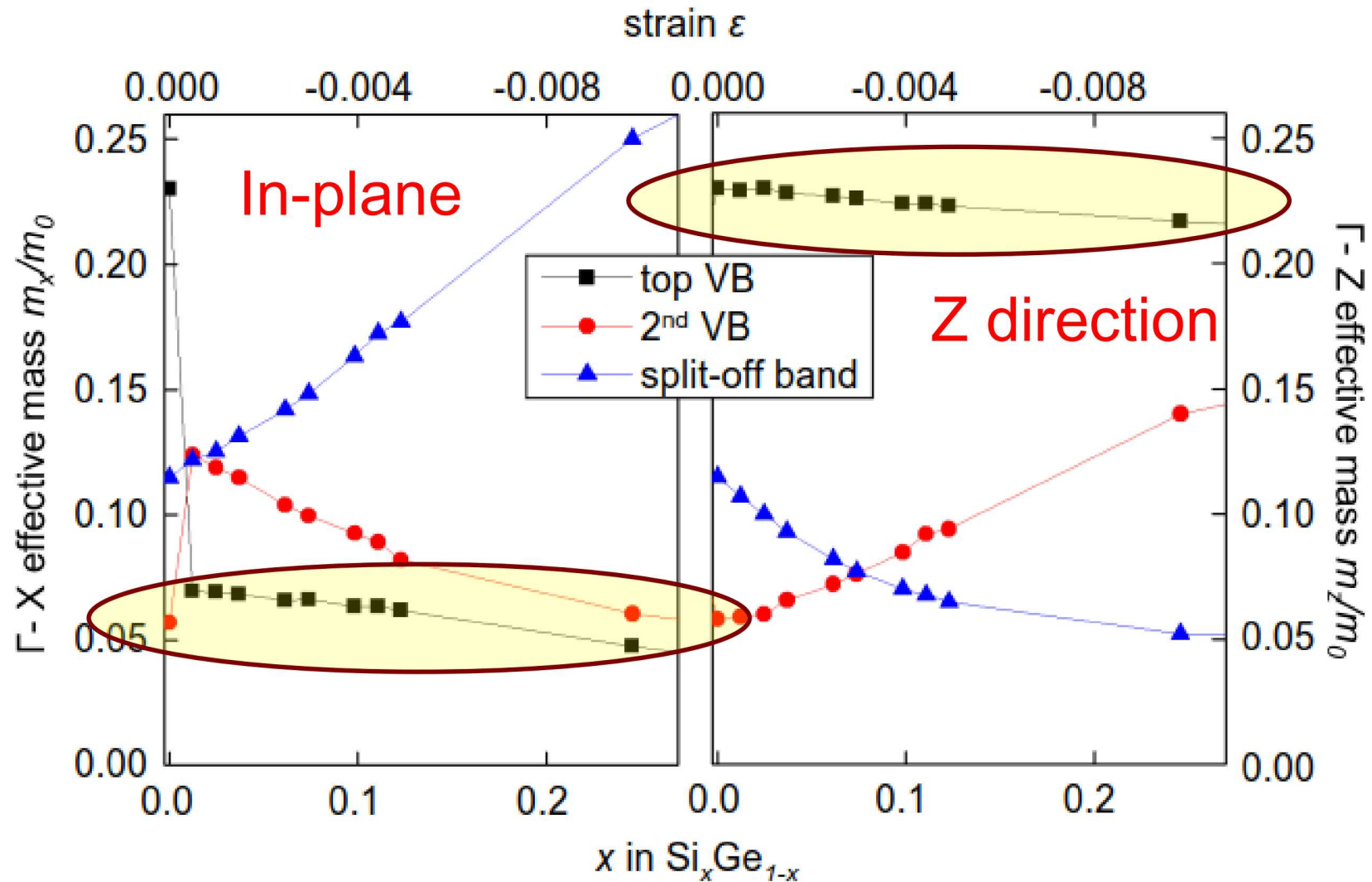
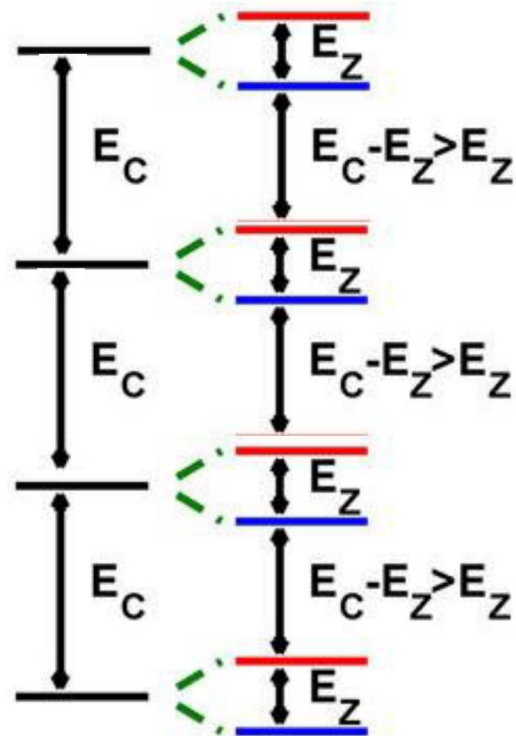


FIG. 8. Figures of constant energy in the (100) plane of k -space for the two fluted energy surfaces which are degenerate at the valence band edge; constants as for germanium.

The quantum Hall effect

In a perpendicular magnetic field, the spectrum of a 2D gas is a series of Landau levels:



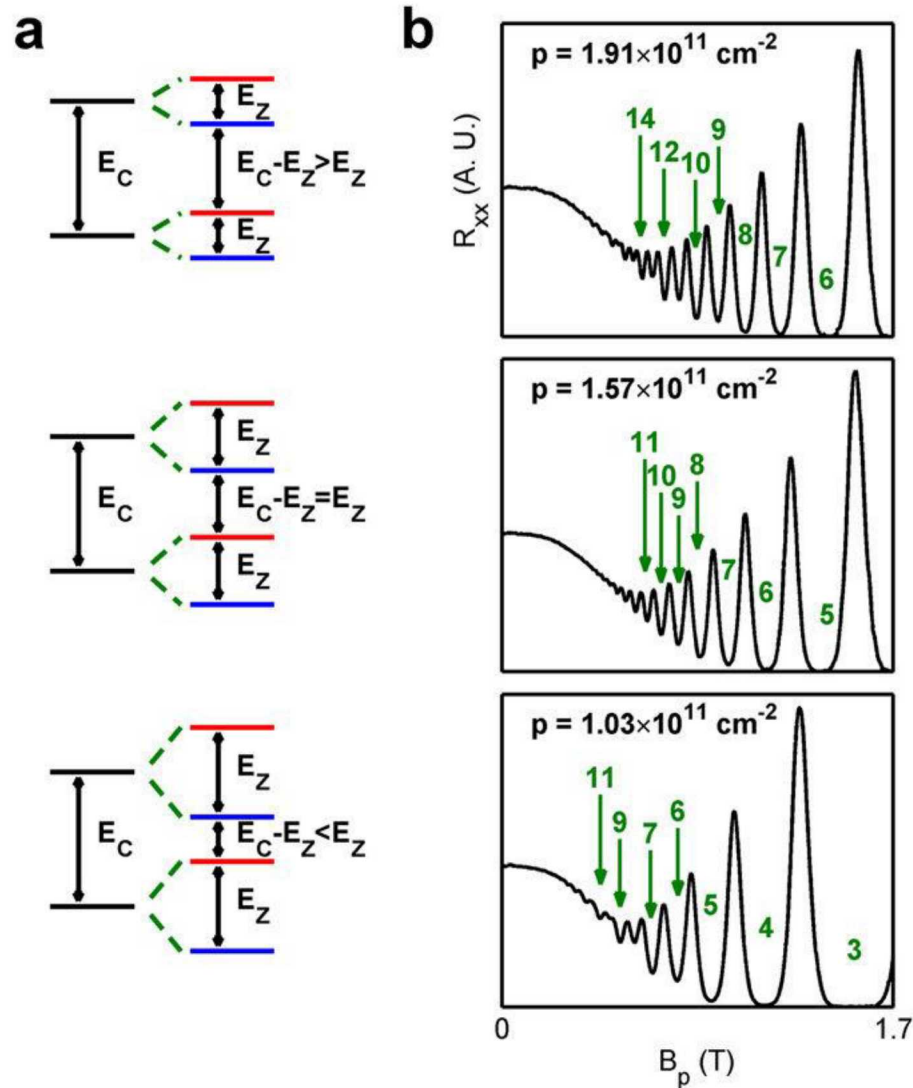
E_C is cyclotron gap: $\hbar e B / (2\pi m^*)$

E_Z is Zeeman gap: $g^* \mu_B$

m^* and g^* are material parameters.

Landau level degeneracy (# electrons / area):
 eB/h

Quantum Hall ferromagnetic transition



In most cases, $E_C \gg E_Z$

$\Rightarrow$ Strong even states, weak odd states

If $E_C \sim 2E_Z$

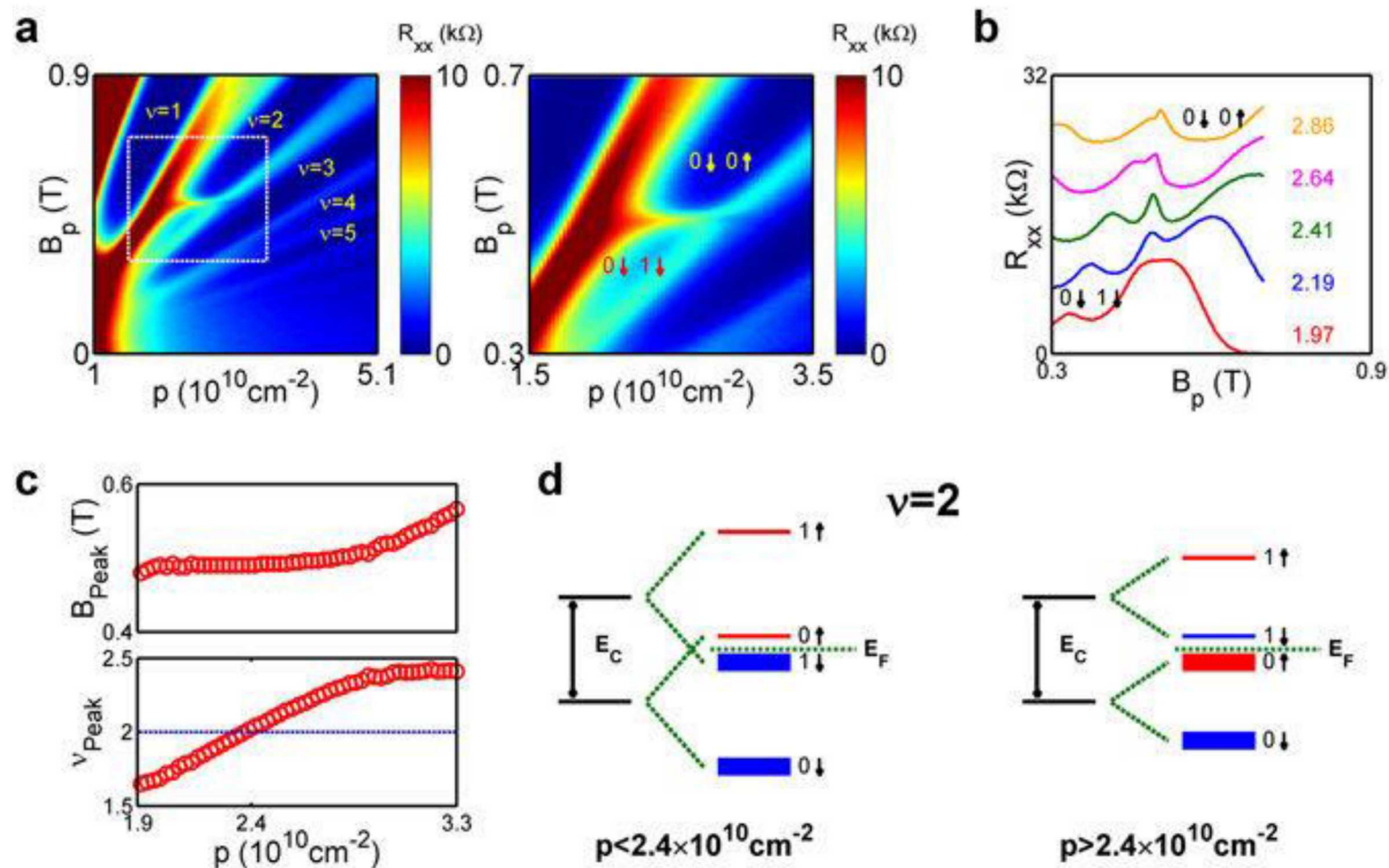
$\Rightarrow$ Strength of even states $\sim$ strength of odd states

If $E_C < 2E_Z$

$\Rightarrow$ Strong odd states, weak even states

E_Z/E_C increases with decreasing density.

Quantum Hall ferromagnetic transition



A spin transition (unpolarized $\leftrightarrow$ polarized) at $\nu=2$ occurs at $p \sim 2.4 \times 10^{10} \text{ cm}^{-2}$.

This transition marks the point where $E_C \sim E_z$

$$\frac{\hbar e B}{(2\pi m^*)} = g^* \mu_B$$

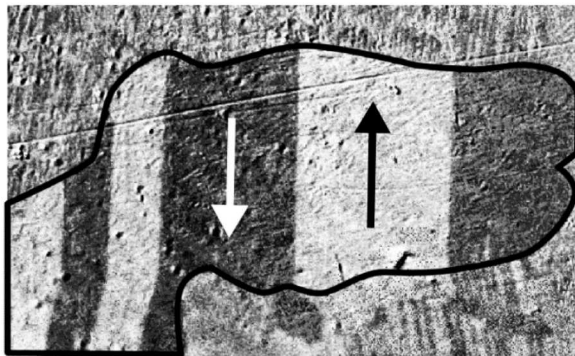
$$\Rightarrow m^* g^* = 2$$

Quantum Hall ferromagnetic transition

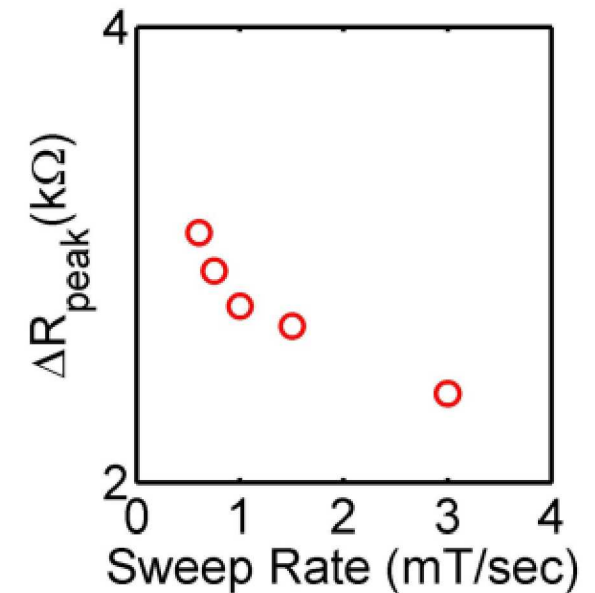
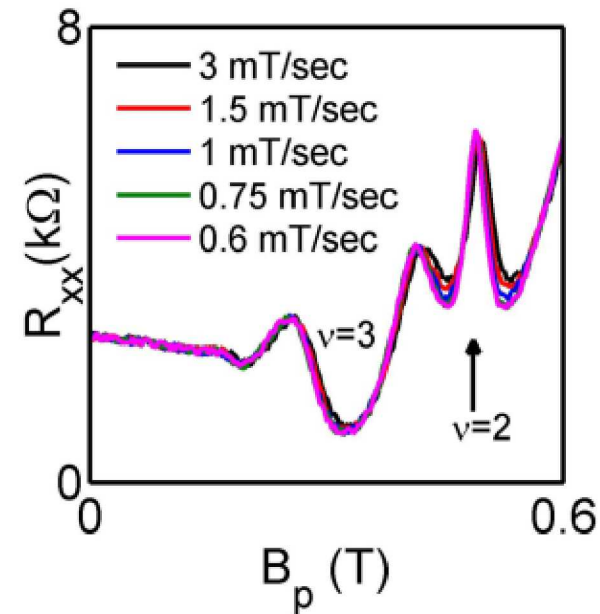
The physical picture of the system at the transition:

micro-domains of different spin configurations. Away from the transition, one spin configuration is preferred. Domains move and merge to minimize surface energy.

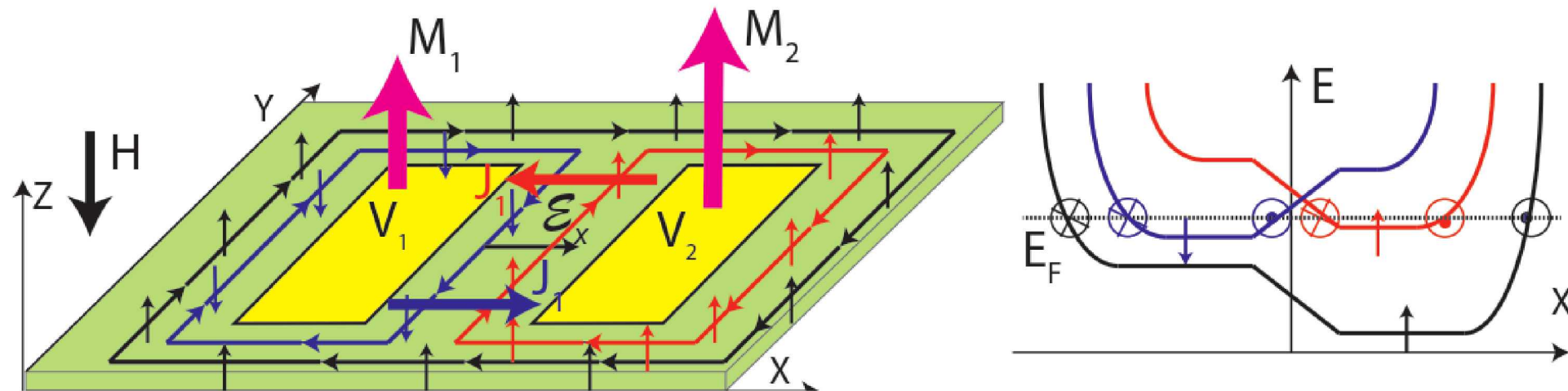
Evidence of micro-domains is found in the time dependence.



by S. Zurek, E. Magnetica, [CC-BY-3.0](https://creativecommons.org/licenses/by/3.0/)



Local gating to create counter-propagating edge states with opposite spins



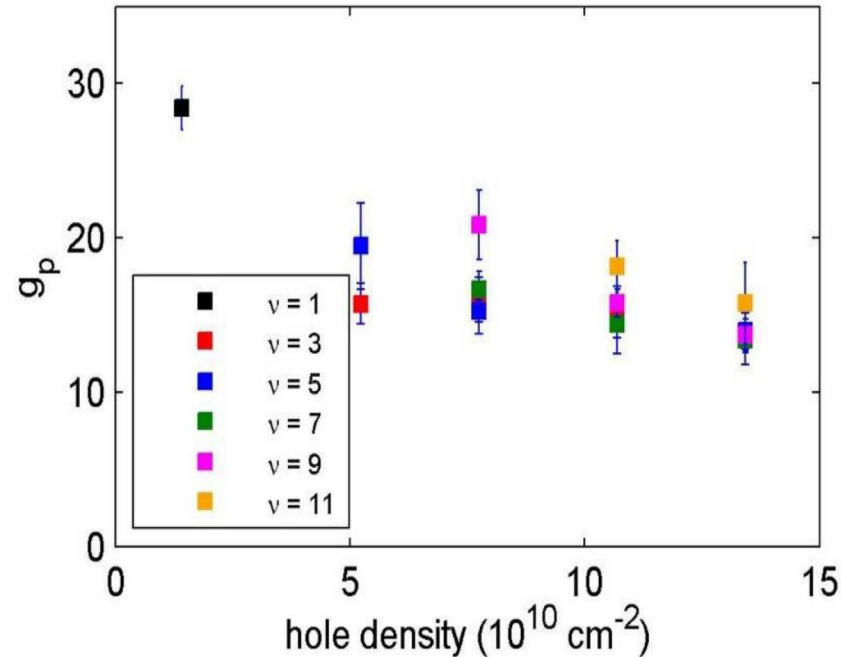
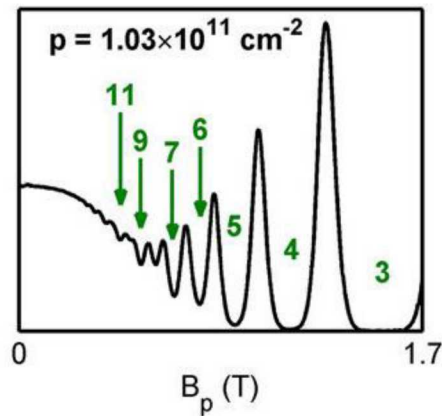
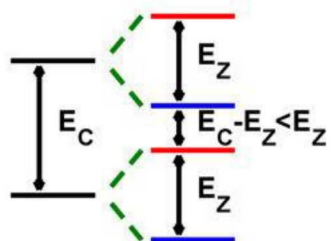
“Impurity-generated non-Abelions”
Simion Phys. Rev. B 97, 245107 (2018)

Physical properties – g factor

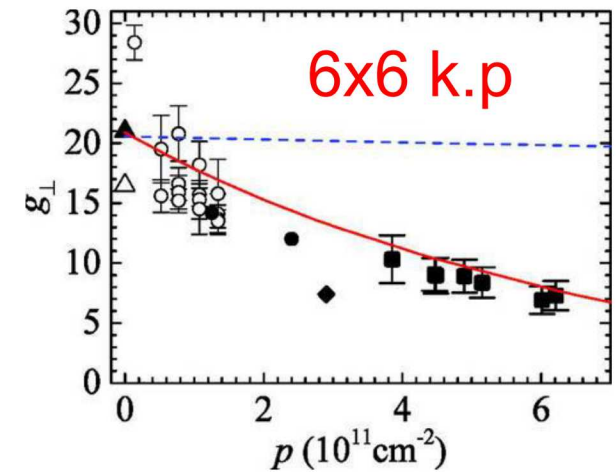
- $\sim 5 - 30$
- $\sim$ density dependent.
- The g factor is large compared to the g factor of electrons in Si (~ 2) and the g factor of electrons in GaAs (~ 0.44).

$$P < 1.6^{11} \text{ cm}^{-2}$$

$$0.5 E_c < E_z < E_c$$



Lu, Appl. Phys. Lett. 111, 102108 (2017)



Drichko J. Appl. Phys. 123, 165703 (2018)

Implications for Quantum Dots

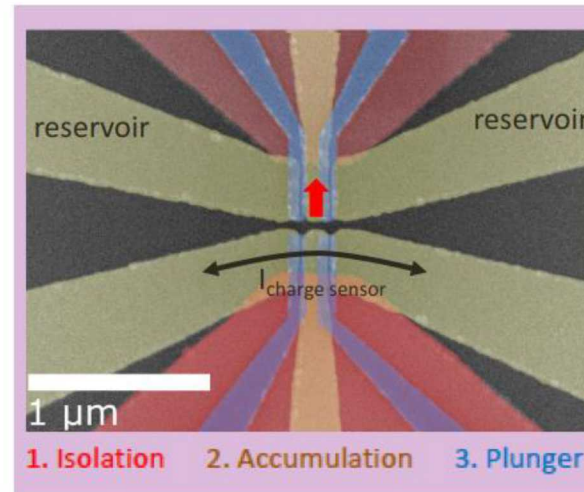
- Low Disorder
 - Help Dot-Dot Coupling
- Small Effective Mass
 - Help Dot-Dot coupling
 - Easier Lithography
- Anisotropic g-factor
 - Large g-factor allows operation at smaller magnetic fields
 - Dot-to-Dot variation is possible
- Strong Spin-Orbit-Coupling
 - Natural mechanism for qubit control
 - Introduces additional noise channel

The effect of confinement on these properties remains largely unexplored



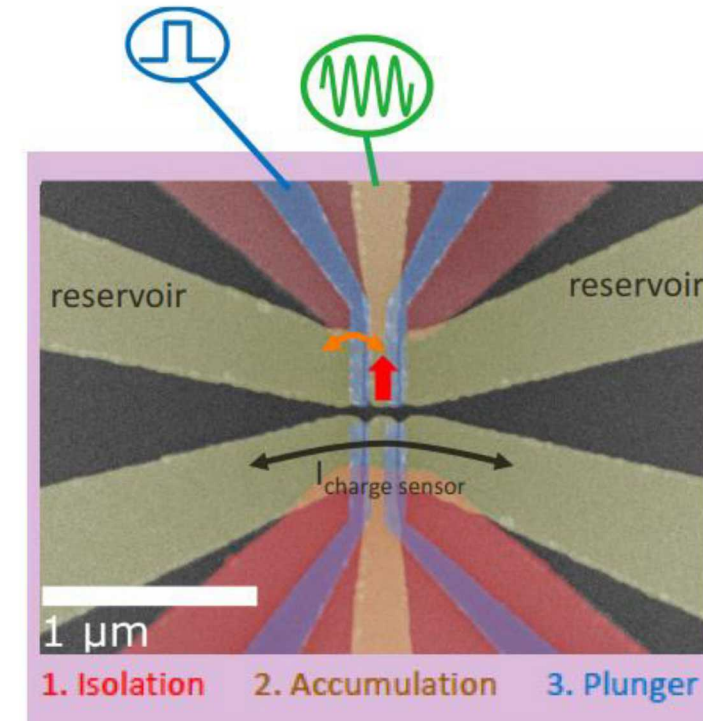
Spin qubits in Ge/SiGe

Surface electrodes used to laterally confine hole

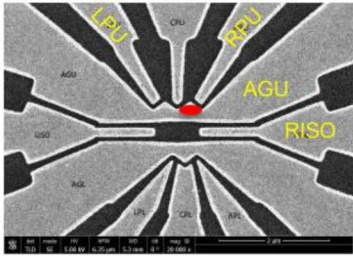


Spin qubits in Ge/SiGe

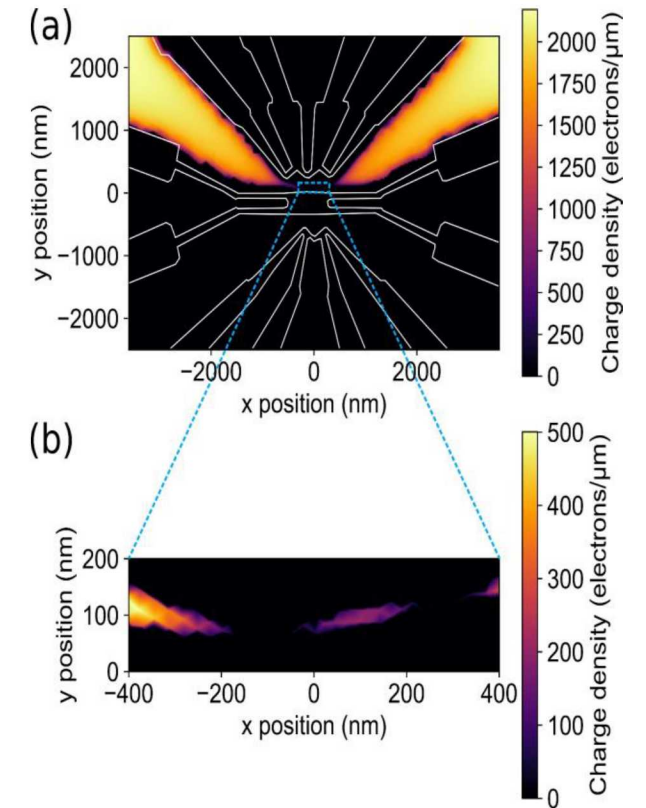
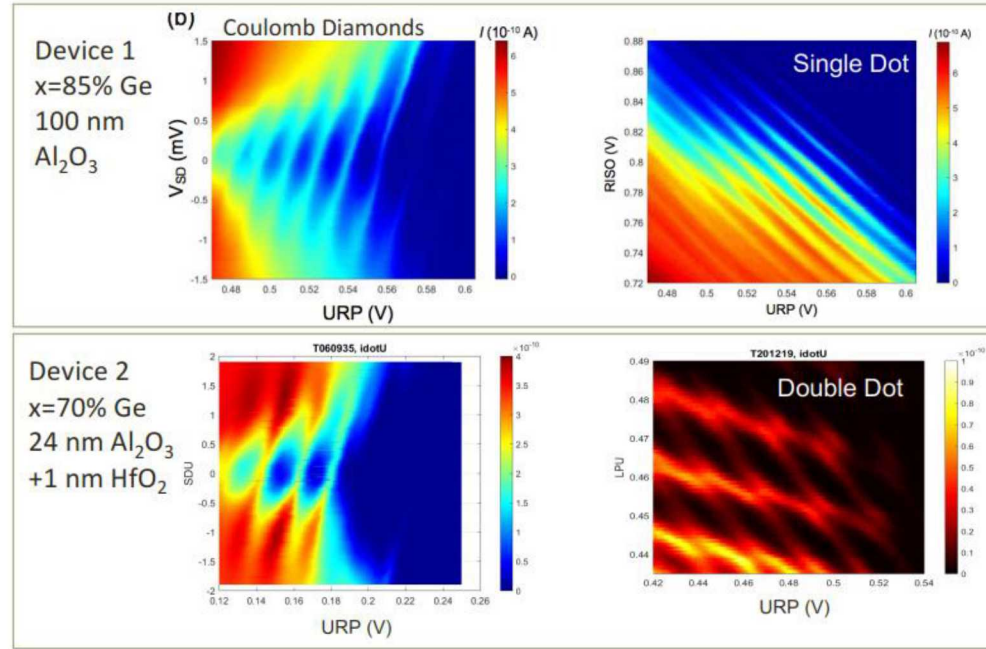
- Single Hole confined to lateral quantum dot
- Spin Qubit States: $m_j = \pm 3/2$
- Qubit readout and initialization through energy selective tunneling to reservoir
- Qubit Control through microwaves applied to gate
- Occupancy detected through nearby charge sensor



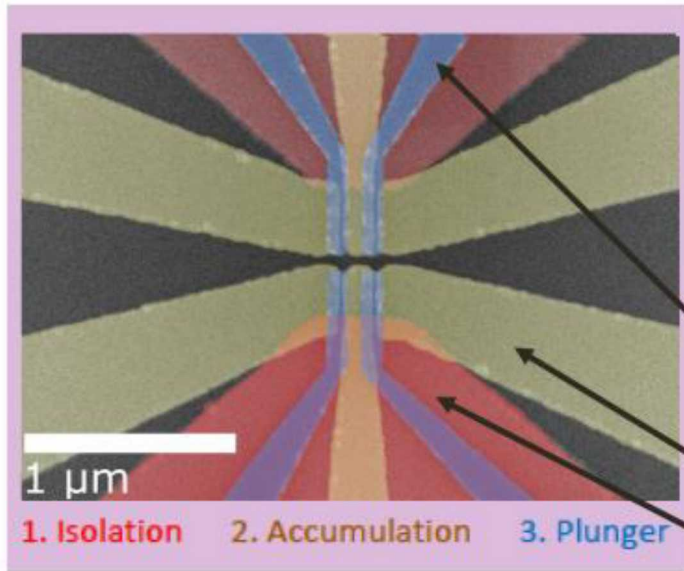
Spin qubits in Ge/SiGe



Single Layer Devices
can be tuned to low-
hole regime in
transport



Spin qubits in Ge/SiGe



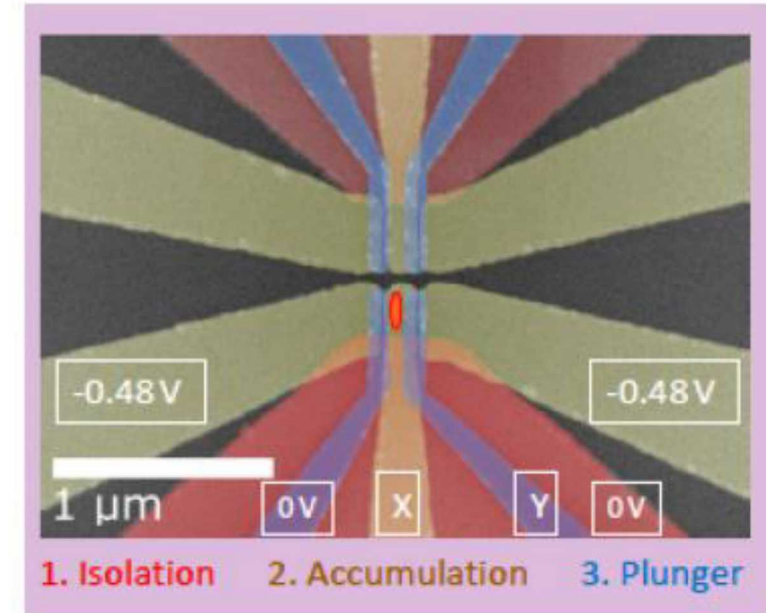
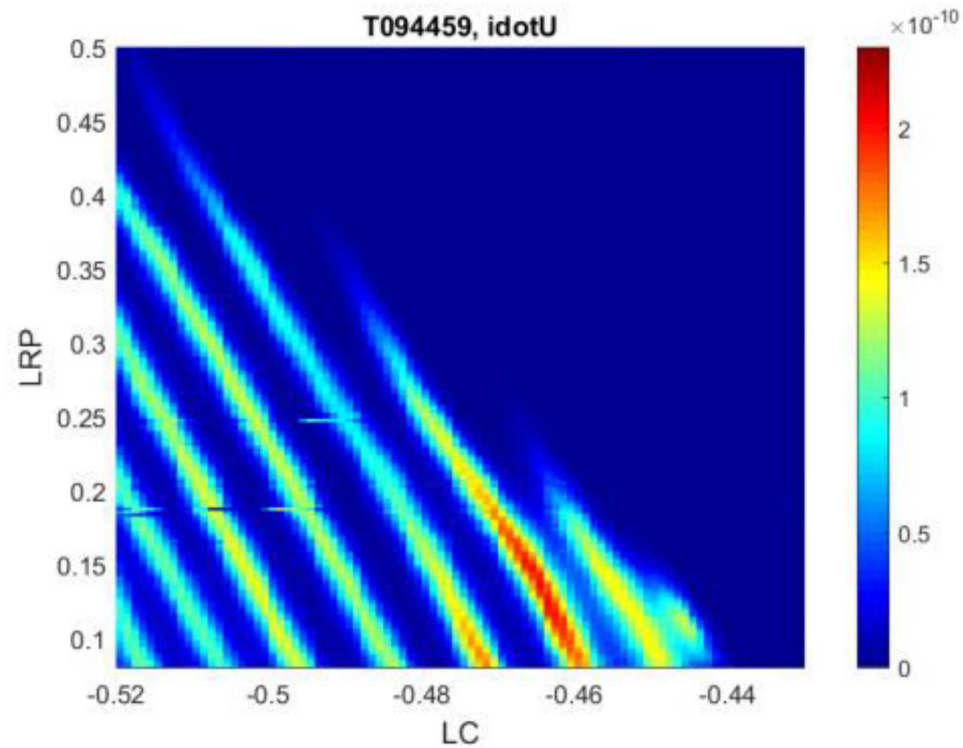
Ga implanted Ohmic contacts

Goals:

- Independent Control of occupation and tunnel barriers
- Tighter Confinement
- Low Capacitance for EDSR



Three Metal Layer Device



Coulomb Blockade observed in
the three-metal-layer devices

Summary

- Induced 2D holes in Ge/SiGe heterostructure field effect transistors demonstrated.
- Device behavior can deviate from thermal equilibrium.
- Physical properties (mass, g factor, spin-orbit coupling strength) characterized.
- Gate controlled quantum Hall ferromagnetic transition observed at low densities. Platform for topological superconductivity?
- Development of spin qubits in Ge/SiGe